

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	"6551871".pn.	US-PGPUB; USPAT	OR	ON	2005/09/07 13:08
L2	79	(hardmask "hard mask") with (implantation implanting) with trench	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:22
L3	7	2 with (photoresist "photo-resist")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:21
L4	3	"6610578".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:07
L5	2643	(hardmask "hard mask") with trench	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:21
L6	549	5 with (photoresist "photo-resist")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:21
L7	2091	"trench formation"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:22
L8	11	6 same 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:52
L9	63	oxide with nitride with (photo-resist photoresist) with trench with (implant\$3 implantation)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 15:53

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	48035	light\$2 with dope\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/30 16:27
S3	143	S1 with pocket	USPAT	OR	OFF	2005/08/04 12:41
S4	9	S3 same block\$3	USPAT	OR	OFF	2005/07/21 12:20
S5	48294	light\$2 with dope\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 12:45
S6	314	S5 with (pocket hallow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 12:59
S7	565	S5 and (pocket hallow) and block\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 14:09
S8	315	S5 with (pocket hallow halow)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 17:29
S9	12	S8 same block\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 13:58
S10	792	(S5 LDD) and (pocket hallow halow) and block\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/04 15:06
S11	42	(S5 LDD) same (pocket hallow halow) same block\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 16:27

S12	750	S10 not S11	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 11:44
S18	2166	(photoresist "photo-resist") with (multilayer "multi-layer" "multiple layers")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 14:40
S19	589	S18 with (block\$3 mask\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 13:19
S20	18	S19 with (dop\$4 implant\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 13:19
S22	18	(hardmask "hard mask") with barrier with (implantation implanting)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/07 14:38
S23	734	(hardmask "hard mask") with "silicon oxide" with "silicon nitride"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 16:34
S24	7	S23 with (implantation implanting)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 16:43
S25	34	S23 same (implantation implanting)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 16:43

S26	27	S25 not S24	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 16:43
S27	5868	silylation	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/06 17:29